Gon-Ho Kim

List of Publications by Year
in descending order

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100	824	566801	610482
papers	citations	15 h-index	24 g-index

101	101	101	817
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Polymer surface modification by plasma source ion implantation. Surface and Coatings Technology, 1997, 93, 261-264.	2.2	118
2	Effect on plasma and etch-rate uniformity of controlled phase shift between rf voltages applied to powered electrodes in a triode capacitively coupled plasma reactor. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2009, 27, 13-19.	0.9	33
3	Global model analysis of negative ion generation in low-pressure inductively coupled hydrogen plasmas with bi-Maxwellian electron energy distributions. Physics of Plasmas, 2015, 22, 033506.	0.7	33
4	Efficacy of a New Navigable Percutaneous Disc Decompression Device (L'DISQ) in Patients with Herniated Nucleus Pulposus Related to Radicular Pain. Pain Medicine, 2011, 12, 370-376.	0.9	31
5	Enhancement of the Virtual Metrology Performance for Plasma-Assisted Oxide Etching Processes by Using Plasma Information (PI) Parameters. IEEE Transactions on Semiconductor Manufacturing, 2015, 28, 241-246.	1.4	30
6	Fabrication of sintered tungsten by spark plasma sintering and investigation of thermal stability. International Journal of Refractory Metals and Hard Materials, 2017, 69, 164-169.	1.7	29
7	Quantitation of the ROS production in plasma and radiation treatments of biotargets. Scientific Reports, 2019, 9, 19837.	1.6	27
8	Influence of H+ ion irradiation on the surface and microstructural changes of a nuclear graphite. Fusion Engineering and Design, 2012, 87, 344-351.	1.0	25
9	Development of the Virtual Metrology for the Nitride Thickness in Multi-Layer Plasma-Enhanced Chemical Vapor Deposition Using Plasma-Information Variables. IEEE Transactions on Semiconductor Manufacturing, 2018, 31, 232-241.	1.4	25
10	High-temperature thermo-mechanical behavior of functionally graded materials produced by plasma sprayed coating: Experimental and modeling results. Metals and Materials International, 2016, 22, 817-824.	1.8	17
11	Plasma uniformity and phase-controlled etching in a very high frequency capacitive discharge. Journal of Applied Physics, 2009, 106, 023303.	1.1	16
12	Frequency and electrode shape effects on etch rate uniformity in a dual-frequency capacitive reactor. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, .	0.9	16
13	Enhancement of deuterium retention in damaged tungsten by plasma-induced defect clustering. Nuclear Fusion, 2017, 57, 126042.	1.6	16
14	Development of Virtual Metrology Using Plasma Information Variables to Predict Si Etch Profile Processed by SF6/O2/Ar Capacitively Coupled Plasma. Materials, 2021, 14, 3005.	1.3	16
15	The bactericidal effect of an atmospheric-pressure plasma jet onPorphyromonas gingivalisbiofilms on sandblasted and acid-etched titanium discs. Journal of Periodontal and Implant Science, 2019, 49, 319.	0.9	16
16	Effects of shroud gas injection on material properties of tungsten layers coated by plasma spraying. Thin Solid Films, 2010, 518, 6369-6372.	0.8	15
17	Characteristics of a non-Maxwellian electron energy distribution in a low-pressure argon plasma. Journal of the Korean Physical Society, 2014, 64, 1819-1827.	0.3	15
18	Effect of annealing with pressure on tungsten film properties fabricated by atmospheric plasma spray. Metals and Materials International, 2014, 20, 1037-1042.	1.8	14

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19	Improvement of mechanical property of air plasma sprayed tungsten film using pulsed electric current treatment. International Journal of Refractory Metals and Hard Materials, 2016, 60, 99-103.	1.7	14
20	Measurement of sheath expansion in plasma source ion implantation. Surface and Coatings Technology, 2001, 136, 97-101.	2.2	12
21	Deposition/erosion and H/D retention characteristics in gaps of PFCs in KSTAR studied by cavity technique. Journal of Nuclear Materials, 2013, 438, S698-S706.	1.3	12
22	The measurement of nitrogen ion species ratio in inductively coupled plasma source ion implantation. Surface and Coatings Technology, 2001, 136, 106-110.	2.2	11
23	Field-emission performance and structural change mechanism of multiwalled carbon nanotubes by oxygen plasma treatment. Thin Solid Films, 2013, 547, 202-206.	0.8	11
24	Metal surface oxidation by using dielectric barrier discharge. Thin Solid Films, 2010, 518, 6394-6398.	0.8	10
25	Mechanism of cone-shaped carbon nanotube bundle formation by plasma treatment. Carbon, 2010, 48, 3864-3873.	5.4	10
26	Effects of metastable species in helium and argon atmospheric pressure plasma jets (APPJs) on inactivation of periodontopathogenic bacteria. Journal of the Korean Physical Society, 2016, 68, 1176-1191.	0.3	10
27	Characteristics of vapor coverage formation on an RF-driven metal electrode to discharge a plasma in saline solution. Plasma Sources Science and Technology, 2012, 21, 055017.	1.3	9
28	Standing wave effect on plasma distribution in an inductively coupled plasma source with a short antenna. Journal Physics D: Applied Physics, 2014, 47, 015205.	1.3	9
29	Determination of electron energy probability function in low-temperature plasmas from current â€“ Voltage characteristics of two Langmuir probes filtered by Savitzkyâ€“Golay and Blackman window methods. Current Applied Physics, 2015, 15, 1173-1183.	1.1	9
30	Design of optical emission spectroscopy based plasma parameter controller for real-time advanced equipment control. Computers and Chemical Engineering, 2017, 100, 38-47.	2.0	9
31	Ion-neutral collision effect on ion-ion two-stream-instability near sheath-presheath boundary in two-ion-species plasmas. Plasma Sources Science and Technology, 2017, 26, 06LT01.	1.3	9
32	Effects of argon and oxygen flow rate on water vapor barrier properties of silicon oxide coatings deposited on polyethylene terephthalate by plasma enhanced chemical vapor deposition. Thin Solid Films, 2010, 518, 1929-1934.	0.8	8
33	Recrystallization of bulk and plasma-coated tungsten with accumulated thermal energy relevant to Type-I ELM in ITER H-mode operation. Journal of Nuclear Materials, 2015, 463, 215-218.	1.3	8
34	Characteristics of a plasma information variable in phenomenology-based, statistically-tuned virtual metrology to predict silicon dioxide etching depth. Current Applied Physics, 2019, 19, 1068-1075.	1.1	8
35	Application of PI-VM for management of the metal target plasma etching processes in OLED display manufacturing. Plasma Physics and Controlled Fusion, 2019, 61, 014032.	0.9	8
36	Predictive control of the plasma processes in the OLED display mass production referring to the discontinuity qualifying PI-VM. Physics of Plasmas, 2020, 27, .	0.7	8

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37	Measurement of expanding plasma sheath from a target biased by a negative pulse with a fast rise time. Journal of Applied Physics, 2003, 93, 1384-1388.	1.1	7
38	Etching of Multi-Walled Carbon Nanotubes Using Energetic Plasma Ions. Japanese Journal of Applied Physics, 2006, 45, 8317-8322.	0.8	7
39	Preliminary test results on tungsten tile with castellation structures in KSTAR. Fusion Engineering and Design, 2014, 89, 1704-1708.	1.0	7
40	Bullet Velocity Distribution of a Helium Atmospheric-Pressure Plasma Jet in Various N₂/O₂ Mixed Ambient Conditions. IEEE Transactions on Plasma Science, 2015, 43, 2054-2063.	0.6	7
41	Deuterium ion irradiation induced blister formation and destruction. Fusion Engineering and Design, 2016, 109-111, 624-628.	1.0	7
42	Hydroxyl Radical Generation on Bubble Surface of Aqua-Plasma Discharge. IEEE Transactions on Plasma Science, 2011, 39, 2658-2659.	0.6	6
43	Dynamic sheath expansion in a non-uniform plasma with ion drift. Plasma Sources Science and Technology, 2011, 20, 045014.	1.3	6
44	Field emission characteristics of cone-shaped carbon-nanotube bundles fabricated using an oxygen plasma. Journal of the Korean Physical Society, 2012, 61, 1083-1087.	0.3	6
45	How to determine the relative ion concentrations of multiple-ion-species plasmas generated in the multi-dipole filament source. Journal Physics D: Applied Physics, 2015, 48, 225201.	1.3	6
46	Vacuum pump age effects by the exposure to the corrosive gases on the Cr etch rate as observed using optical emission spectroscopy in an Ar/O2/Cl2 mixed plasma. Thin Solid Films, 2016, 603, 154-159.	0.8	6
47	Cause analysis of the faults in HARC etching processes by using the PIâ€VM model for OLED display manufacturing. Plasma Processes and Polymers, 2019, 16, 1900030.	1.6	6
48	Design of a self-tuning adaptive model predictive controller using recursive model parameter estimation for real-time plasma variable control. Computers and Chemical Engineering, 2019, 123, 126-142.	2.0	6
49	Plasma information-based virtual metrology (PI-VM) and mass production process control. Journal of the Korean Physical Society, 2022, 80, 647-669.	0.3	6
50	Numerical investigation of plasma recovery in plasma source ion implantation. Thin Solid Films, 2012, 521, 197-200.	0.8	5
51	Driving frequency dependency of gas species in the bubble formation for aqua-plasma generation. Current Applied Physics, 2013, 13, S54-S58.	1.1	5
52	Analysis of Langmuir Probe Data Using Wavelet Transform. IEEE Transactions on Plasma Science, 2004, 32, 355-361.	0.6	4
53	Self-consistent circuit model for plasma source ion implantation. Review of Scientific Instruments, 2008, 79, 02C502.	0.6	4
54	Numerical Analysis on the Electrical and Thermal Flow Characteristics of Ar-N2 Inductively Coupled Plasma Torch System. Journal of the Korean Physical Society, 2018, 72, 755-764.	0.3	4

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55	Micro-range uniformity control of the etching profile in the OLED display mass production referring to the PI-VM model. Physics of Plasmas, 2021, 28, 103505.	0.7	4
56	The effect of plasma exposure and annealing atmosphere on shallow junction formation using plasma source ion implantation. Surface and Coatings Technology, 2002, 157, 19-25.	2.2	3
57	Time-resolved plasma measurement in a high-power pulsed ICP source for large area. Surface and Coatings Technology, 2004, 186, 161-164.	2.2	3
58	Low-energy D+ and H+ ion irradiation effects on highly oriented pyrolytic graphite. Journal of Applied Physics, 2013, 114, 214310.	1.1	3
59	Investigation of SOL plasma interaction with graphite PFC. Journal of Nuclear Materials, 2015, 463, 753-756.	1.3	3
60	Optimal Parameters for Intervertebral Disk Resection Using Aqua-Plasma Beams. Journal of Neurological Surgery, Part A: Central European Neurosurgery, 2019, 80, 034-038.	0.4	3
61	Characteristics of Molybdenum as a Plasma-Generating Electrode. Science of Advanced Materials, 2016, 8, 1844-1847.	0.1	3
62	Population Kinetics Modeling of Low-Temperature Argon Plasma. Atoms, 2021, 9, 100.	0.7	3
63	Development of model predictive control of fluorine density in SF6/O2/Ar etch plasma by oxygen flow rate. Current Applied Physics, 2022, 36, 183-186.	1.1	3
64	Design and operation of an Omegatron mass spectrometer for measurements of positive and negative ion species in electron cyclotron resonance plasmas. Plasma Sources Science and Technology, 2000, 9, 97-107.	1.3	2
65	Investigation of Current on the Conducting Target Biased with a Large Negative Potential in the Non-Uniform Plasma. Japanese Journal of Applied Physics, 2006, 45, L686-L689.	0.8	2
66	Hydrogen Adsorption Property of Pore Structure Controlled Single-Walled Carbon Nanotubes with Electron Irradiation. Journal of Physical Chemistry C, 2010, 114, 13975-13978.	1.5	2
67	Experimental investigation of plasma recovery during the pulse-off time in plasma source ion implantation. Thin Solid Films, 2013, 547, 13-16.	0.8	2
68	Characteristics of OH* Generation in Pin-to-Electrolyte Discharges. IEEE Transactions on Plasma Science, 2014, 42, 2814-2815.	0.6	2
69	Characterization of Twoâ€“Radio-Frequencyâ€“Driven Dual Antenna Negative Hydrogen Ion Sources. Fusion Science and Technology, 2015, 68, 105-112.	0.6	2
70	Observation of oversaturation-induced defect formation in tungsten irradiated by low energy deuterium ion. Journal of the Korean Physical Society, 2016, 69, 518-524.	0.3	2
71	Optical diagnostics for the highly populated tail of an electron energy distribution function in very-high-frequency capacitively coupled plasma using spin- and dipole-forbidden lines. Journal Physics D: Applied Physics, 2017, 50, 225201.	1.3	2
72	Safety evaluation of atmospheric pressure plasma jets in in vitro and in vivo experiments. Journal of Periodontal and Implant Science, 2021, 51, 213.	0.9	2

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73	Bias Frequency Effect on the Accuracy of Floating Probe Measurement. Journal of the Korean Physical Society, 2009, 55, 1841-1848.	0.3	2
74	Effect of Helmholtz Oscillation on Auto-shroud for APS Tungsten Carbide Coating. Journal of Thermal Spray Technology, 2013, 22, 756-763.	1.6	1
75	Laser-Assisted HÎ¼ Spectroscopy for Measurement of Negative Ion Density in a Hydrogen Plasma. Fusion Science and Technology, 2015, 68, 171-177.	0.6	1
76	Determination of electron energy distribution function shape for non-Maxwellian plasmas using floating harmonics method. Journal Physics D: Applied Physics, 2015, 48, 022001.	1.3	1
77	Development of plasma sources and diagnostics for the simulation of fusion edge plasmas. Journal of the Korean Physical Society, 2022, 80, 735-758.	0.3	1
78	Calculation of transport parameters in KT-1 tokamak edge plasma. Current Applied Physics, 2001, 1, 497-503.	1.1	0
79	A study on m=1 mode helicon wave propagation in a weakly magnetized inductively coupled plasma source. , 0, , .		0
80	Development of in-situ plasma density monitoring method in inductively coupled plasma. , 0, , .		0
81	O/sub 2/-gas flow-rate effect on the atmospheric dielectric barrier discharge plasma. , 0, , .		0
82	Study on the optimum operating condition of the dielectric barrier discharge (DBD) for removing photoresist. , 0, , .		0
83	Study on magnetized inductively coupled plasma with Nagoya III antenna. , 0, , .		0
84	Time transient sheaths in collisionless and collisional plasmas. , 0, , .		0
85	Use of rotating compensator spectroscoic ellipsometry for monitoring the photoresist etching on Si wafer. , 2003, , .		0
86	Ion irradiation effects on the structural deformation of multi-walled carbon nanotubes. , 0, , .		0
87	Structural Deformation of Carbon Nanotubes using Energetic Plasma Ion Irradiation. IEEE International Conference on Plasma Science, 2005, , .	0.0	0
88	Determination of Plasma Current on the Electrode Biased a High Negative Potential. , 2006, , .		0
89	Analysis of Electron Energy Distribution Function from a Langmuir Probe Data Using the Bi-orthogonal Wavelet Transform. , 2006, , .		0
90	Plasma Flow Characteristics in a Spray-Type Dielectric Barrier Discharge Reactor. IEEE Transactions on Plasma Science, 2009, 37, 773-784.	0.6	0

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91	Effects of discharge gas metastable energy level on the nitric oxide radical generation in Atmospheric Pressure Plasma Jet for oral bacteria removal. , 2012, , .		0
92	Analysis on Interface Diffusion-Induced Embrittlement between Tungsten and Graphite with Reactive Diffusion Barrier Model. Fusion Science and Technology, 2015, 68, 113-119.	0.6	0
93	Improvement of dynamic range of electron energy probability function from two asymmetrical collecting area probe data filtered by Savitzky-Golay and Blackman window methods. , 2015, , .		0
94	Observation of two-ion-stream instability in sheath-presheath transition region by LIF measurement. , 2015, , .		0
95	Real-time Etch Control to Reduce First Wafer Effect in SF<inf>6</inf>/O<inf>2</inf>/Ar Plasma. , 2018, , .		0
96	Recursive Model Estimation for the Plasma Parameters Quality Control. Computer Aided Chemical Engineering, 2018, 43, 279-284.	0.3	0
97	Online System Identification for the Real Time Control of the Plasma Parameters. Computer Aided Chemical Engineering, 2018, , 2041-2046.	0.3	0
98	Phenomenology-based model predictive control of electron density in Ar/SF6 capacitively coupled etch plasma. Journal of the Korean Physical Society, 2022, 80, 233-240.	0.3	0
99	Sparse Bayesian long short-term memory networks for computationally efficient stochastic modeling of plasma etch processes. Computers and Chemical Engineering, 2022, 159, 107696.	2.0	0
100	Simulations of fusion edge plasmas by linear plasma devices: physics and plasmaâ€“material interactions. Journal of the Korean Physical Society, 0, , 1.	0.3	0